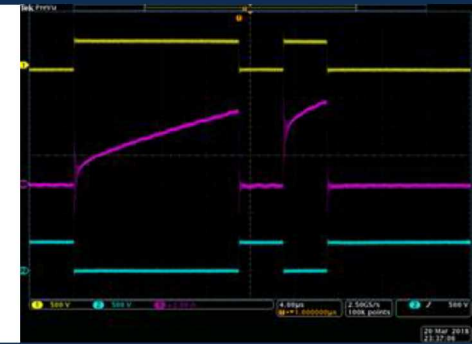
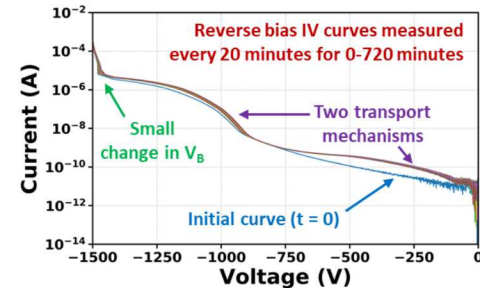
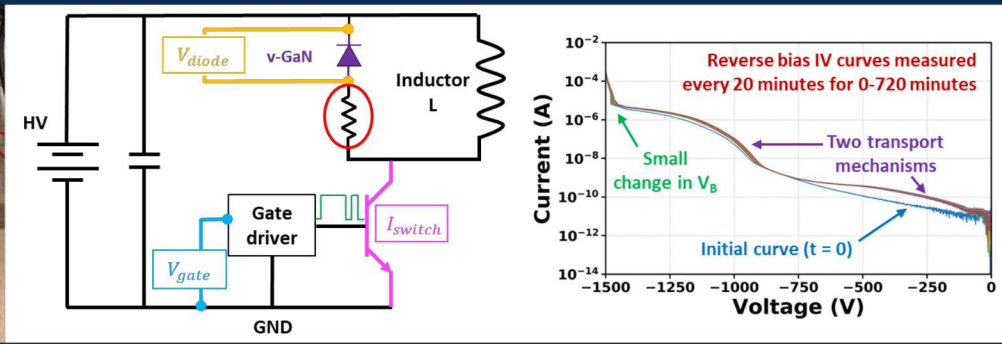


Exceptional service in the national interest



Hard-Switching Reliability Studies of 1200 V Vertical GaN PiN Diodes

R. Kaplar¹, O. Slobodyan¹, J. Flicker¹, S. Sandoval², C. Matthews², M. van Heukelom¹, T. Smith¹, S. Atcity¹, S. Khalil³, and S. Bahl⁴

1 – Sandia National Laboratories, Albuquerque, NM

2 – Sandia National Laboratories, Albuquerque, NM and University of Arkansas, Fayetteville, AR

3 – Infineon, El Segundo, CA

4 – Texas Instruments, Santa Clara, CA



MRS[®]
SPRING MEETING
& EXHIBIT

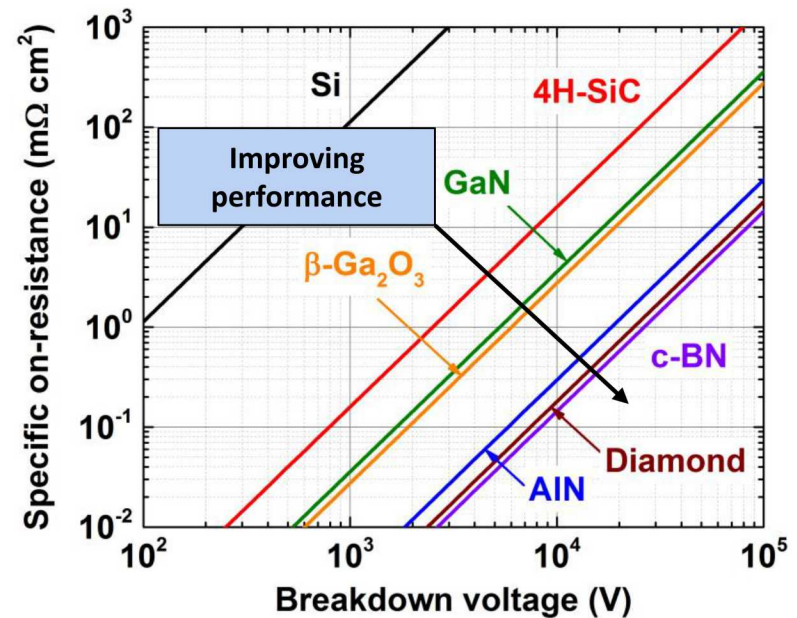
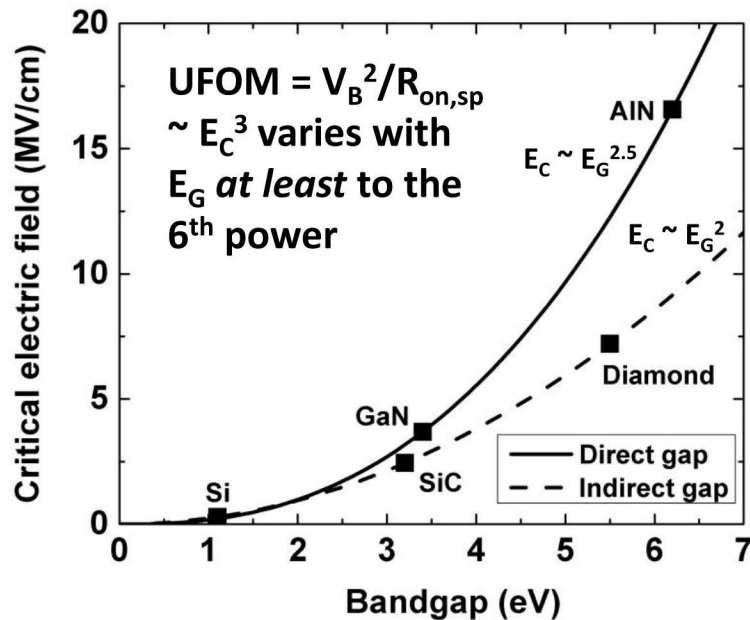
Phoenix, AZ
April 4, 2018

III-Nitride Semiconductors Are Outstanding Materials for Power Devices

Fundamental Materials Capabilities

Property	Conventional		WBG	UWBG	
	Si	GaAs	4H-SiC	GaN	AlN
Bandgap (eV)	1.1	1.4	3.3	3.4	6.0
Critical Electric Field (MV/cm)	0.3	0.4	2.0	4.9	13.0

III-N



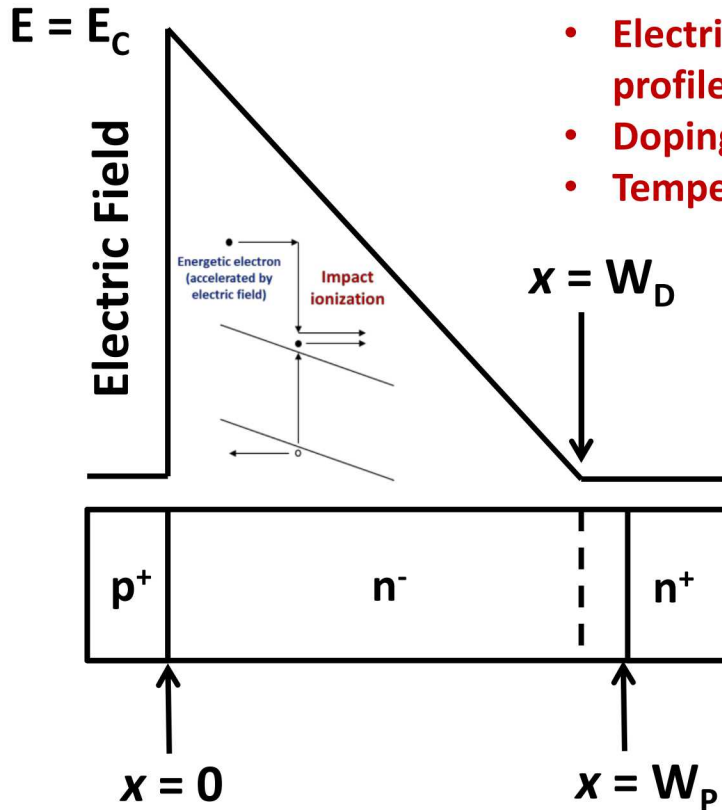
Hudgins et al., *IEEE Trans. Pwr. Elec.* 18, 907 (2003)
 J. Y. Tsao et al., *Adv. Elec. Mat.* 4, 1600501 (2018)

$$\text{Unipolar FOM} = V_B^2/R_{on,sp} = \epsilon\mu_n E_C^3/4$$

Critical Electric Field Is Not a Constant

Critical electric field depends on:

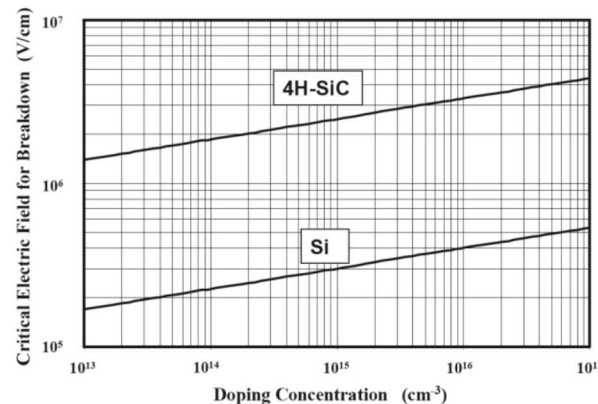
- Electric field profile (E_C is formally defined for triangular field profile in non-punch-through drift region)
- Doping (impurity scattering competes with impact ionization)
- Temperature (phonon scattering competes with impact ionization)



The critical electric field is defined as the peak electric field that leads to avalanche breakdown in a 1D model

$$M(x) = \frac{\exp\left[\int_0^x (\alpha_p - \alpha_n) dx'\right]}{1 - \int_0^{W(E_C)} \alpha_n \exp\left[\int_0^x (\alpha_p - \alpha_n) dx'\right] dx}$$

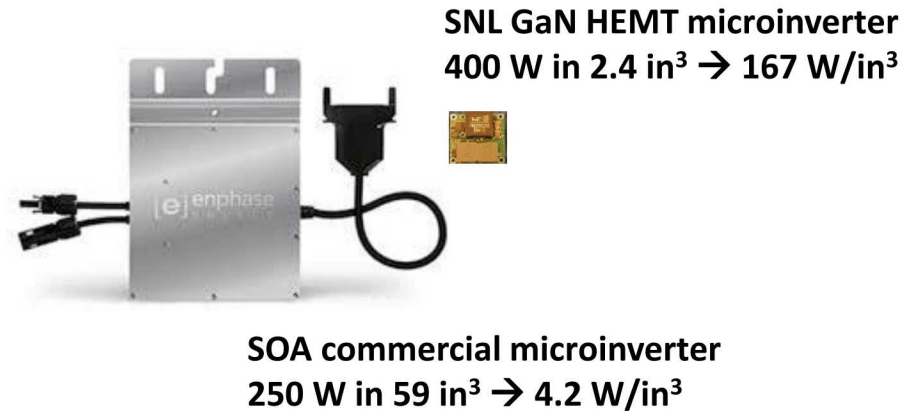
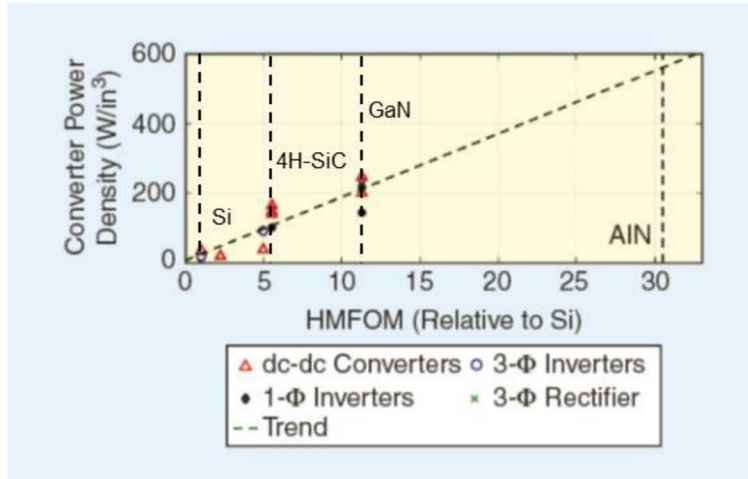
Avalanche occurs when denominator approaches zero



Impact ionization and critical electric field are not well characterized for GaN or other III-N semiconductors!

Impact of WBG Devices on Power Conversion Systems

$$\text{Huang Material FOM} = E_c \mu_n^{1/2}$$



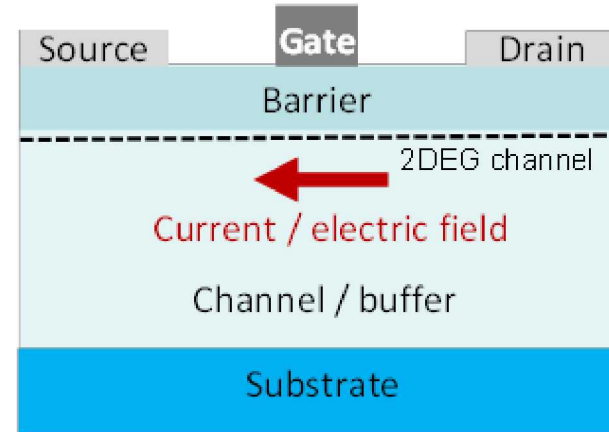
Considers conduction and switching losses

- **WBG semiconductor devices can have a strong impact on system size and weight due to reduced size of passive components and reduced thermal management requirements**
- ***But their reliability is less well characterized than traditional Si devices, especially for GaN and for realistic switching conditions***

Vertical GaN Power Devices

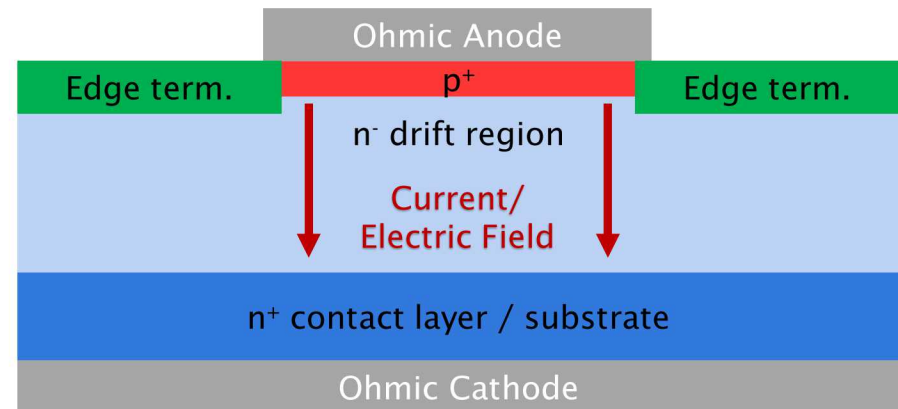
➤ **Historically, GaN power devices have lateral architecture**

- Limits voltage hold-off to $\approx < 650$ V due to electric field management
- High frequency, but no avalanche



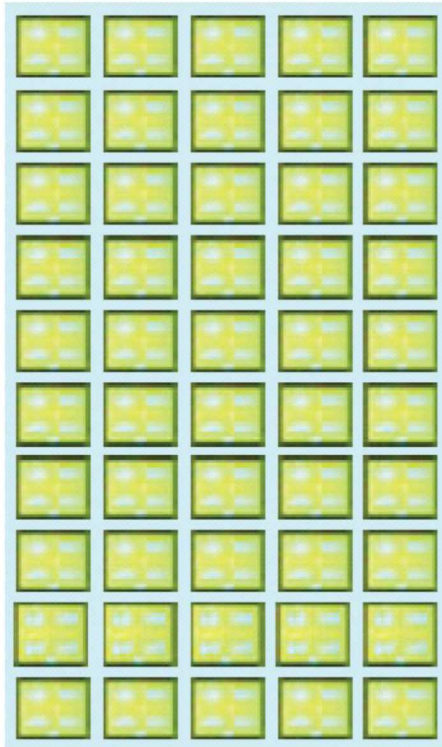
➤ **Vertical GaN (v-GaN) devices are now becoming available**

- Better potential for high-voltage operation ($\approx > 1200$ V)
- Avalanche capability
- Reliability and switching performance are largely *uncharacterized* in literature



Area Advantage of Vertical GaN

For a given on-resistance (R_{on}) of $10\text{m}\Omega$:

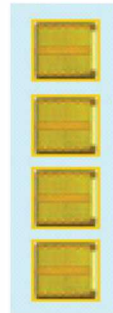


500m Ω , 50 chips
Si-MOSFET

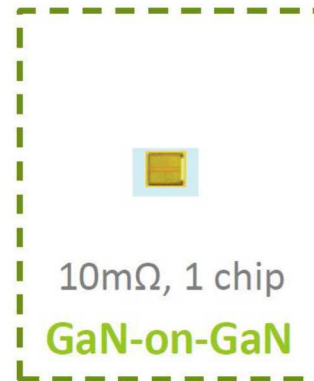
➤ **Tested Avogy vertical GaN PiN diodes**

- 0.72 mm² area
- 1200 V, 15 A peak forward current

*GaN-on-GaN lowers die cost
while improving $R_{on} \times C_{off}$
switching characteristic*



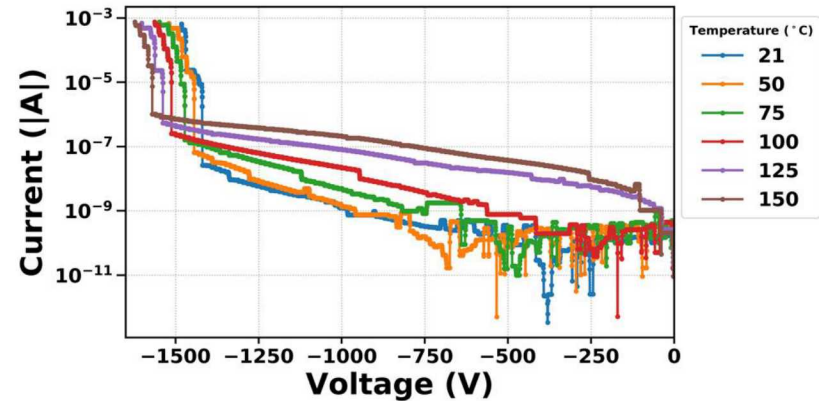
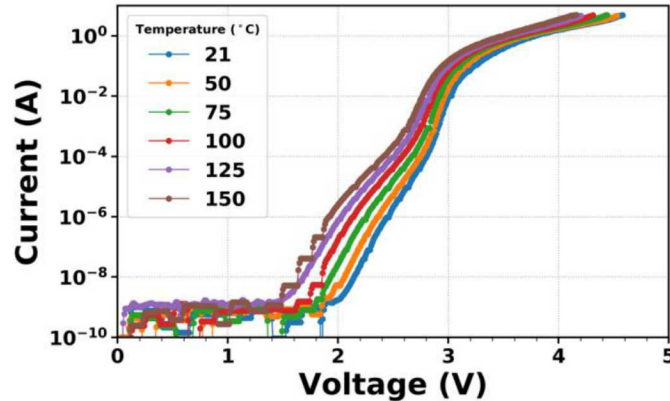
40m Ω , 4 chips
**GaN-on-Si
SiC**



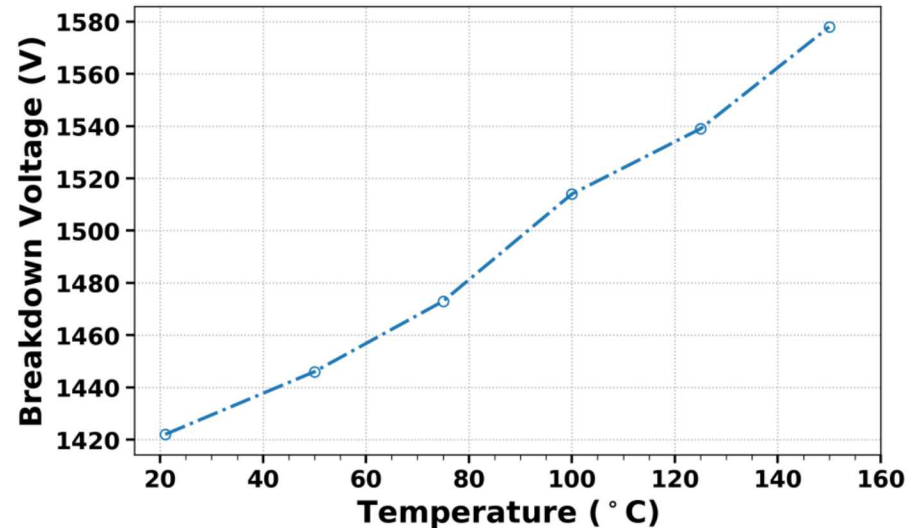
10m Ω , 1 chip
GaN-on-GaN

*The devices tested
were obtained from I.
Kizilyalli and O. Aktas
at Avogy, and were
fabricated under the
ARPA-E SWITCHES
program managed by
Dr. Tim Heidel*

Current-Voltage Characteristics of ν -GaN PiN Diodes

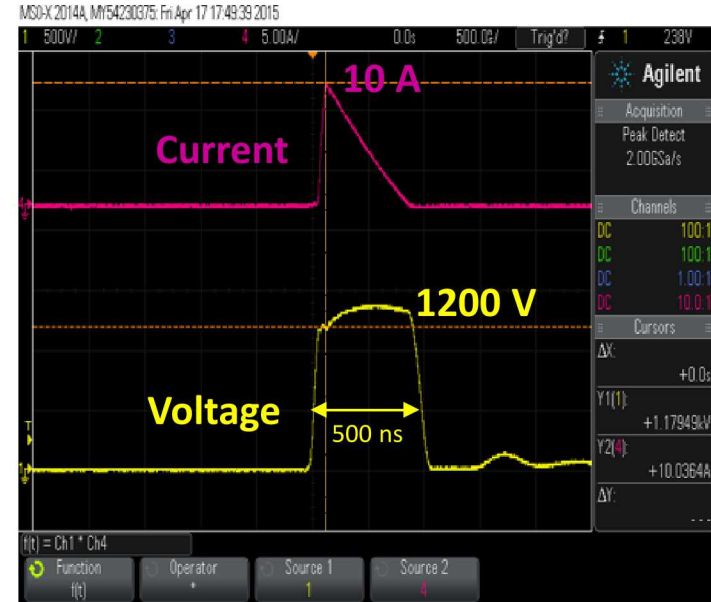
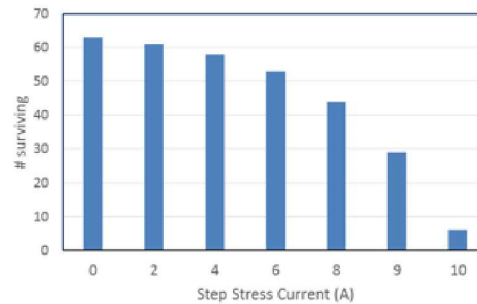
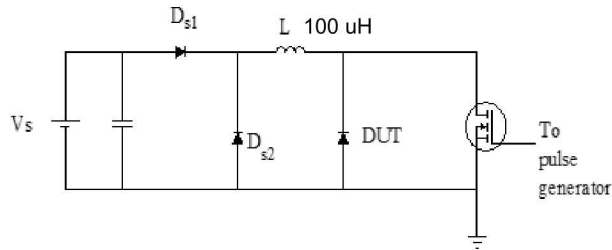


- Forward and reverse I-V curves measured
 - Room T to 150°C, 25°C steps
- Confirmed datasheets
- Avalanche breakdown
 - Positive temperature coefficient
 - Repeatable and non-destructive



Vertical GaN PiN Diodes Show Avalanche Ruggedness

Avalanche test circuit



GaN vertical p-n diodes ($A=0.36 \text{ mm}^2$) can withstand 10^5 / 5kHz pulses at 10A and 1200V for 10's of ns

- 1200 V GaN PiN diode, 0.36 mm^2 , packaged in TO220
- Avalanche peak power 12 kW → Energy per pulse 3 mJ
- Avalanche current increased after each 10^5 pulse cycle
- Number of surviving parts recorded; no parametric degradation for survivors

Double-Pulse Test Circuit

- DPTC is usually used to characterize switching of inductively-loaded power transistors
 - But for this work, we use a known good switch and characterize the diode
- Two modes of operation
 - Transient (double-pulse): Traditional use, characterizes switching behavior
 - Steady-state (continuous): New use for reliability testing
- *Realistic evaluation of reliability in a switching power circuit*

Circuit Diagram

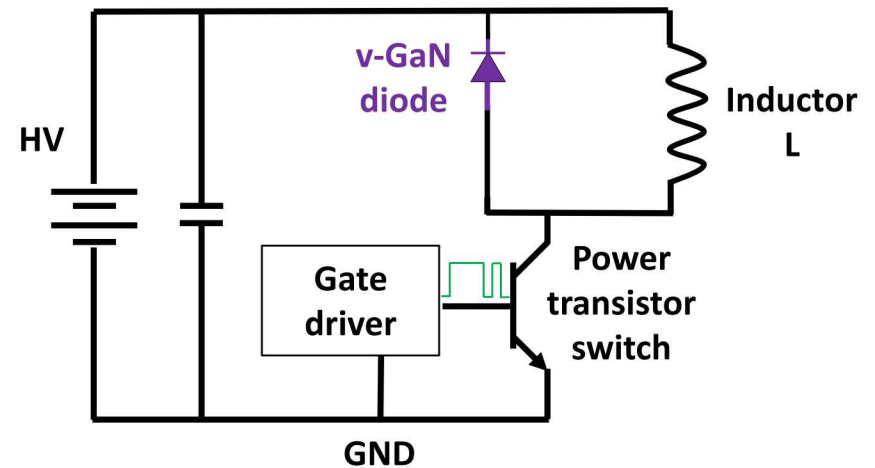


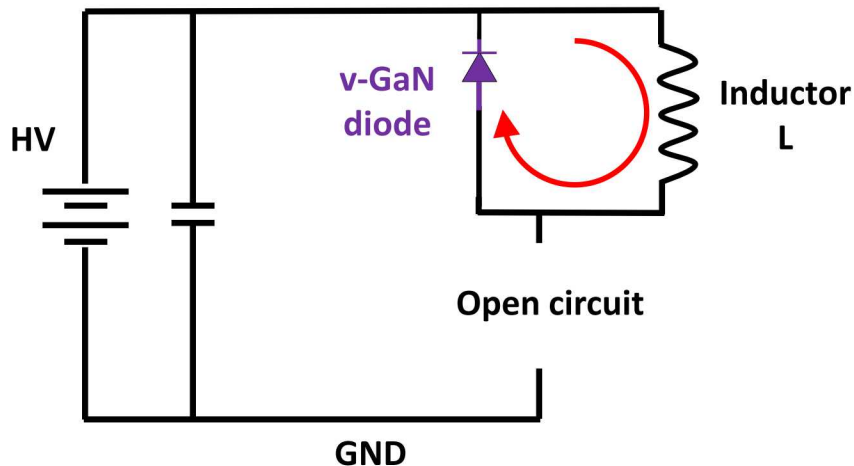
Photo of test circuit



Operation of DPTC

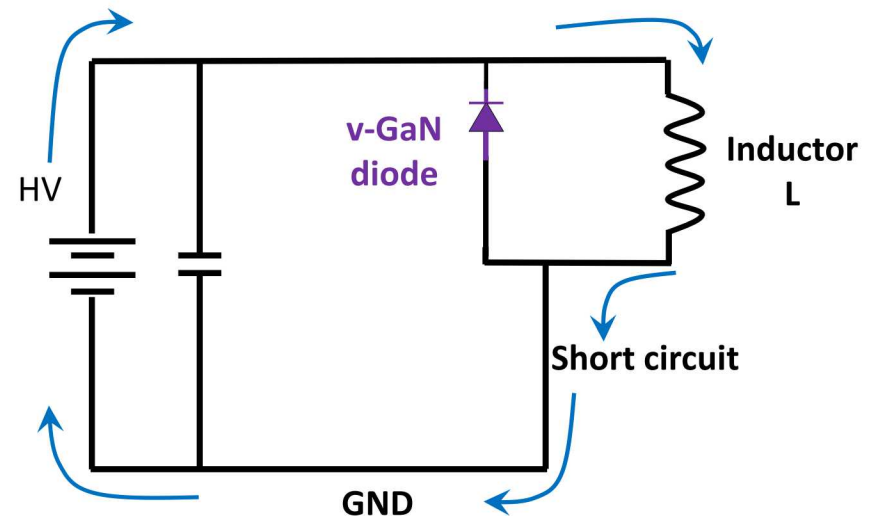
The circuit has two configurations, depending on whether the switch is open (off-state) or closed (on-state)

Switch open (off-state)



- Supply voltage dropped across open circuit
- Diode is forward biased (few volts) so small voltage across inductor
- Inductor current is therefore constant and circulates around diode-inductor loop

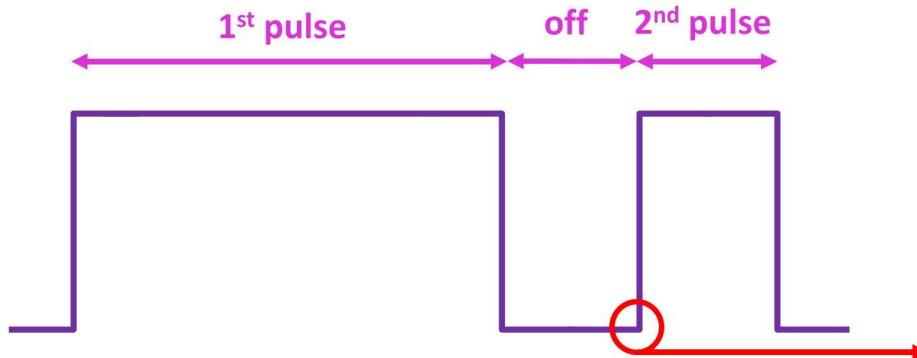
Switch closed (on-state)



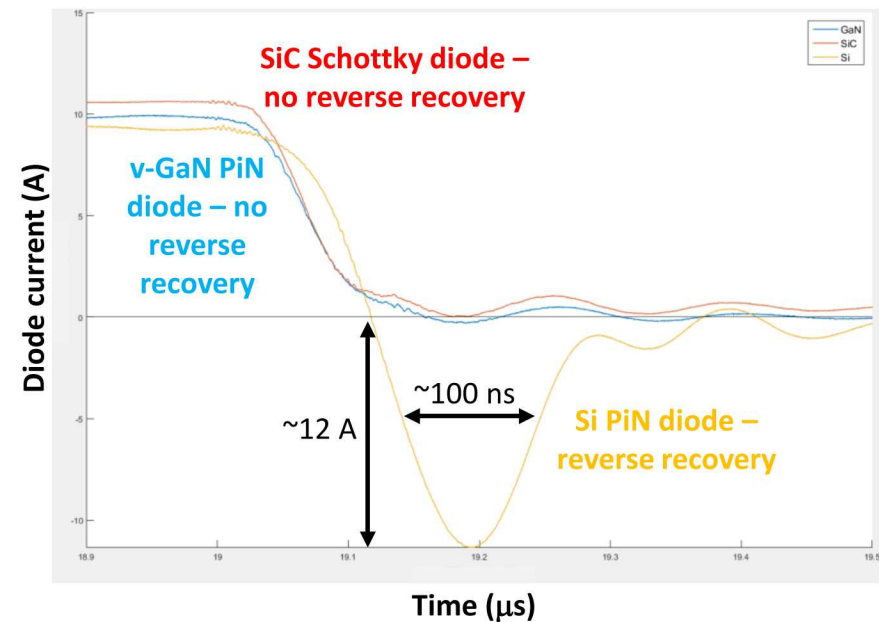
- Supply voltage dropped across reverse-biased diode, leakage current only
- Large voltage across inductor equal to diode reverse bias voltage
- Inductor current ramps up linearly and flows around circuit

Switching Characterization Using DPTC

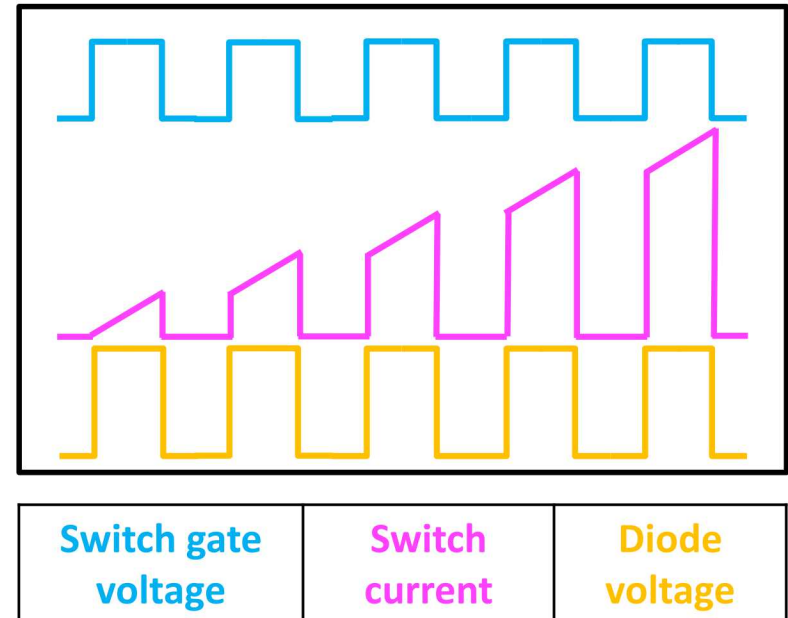
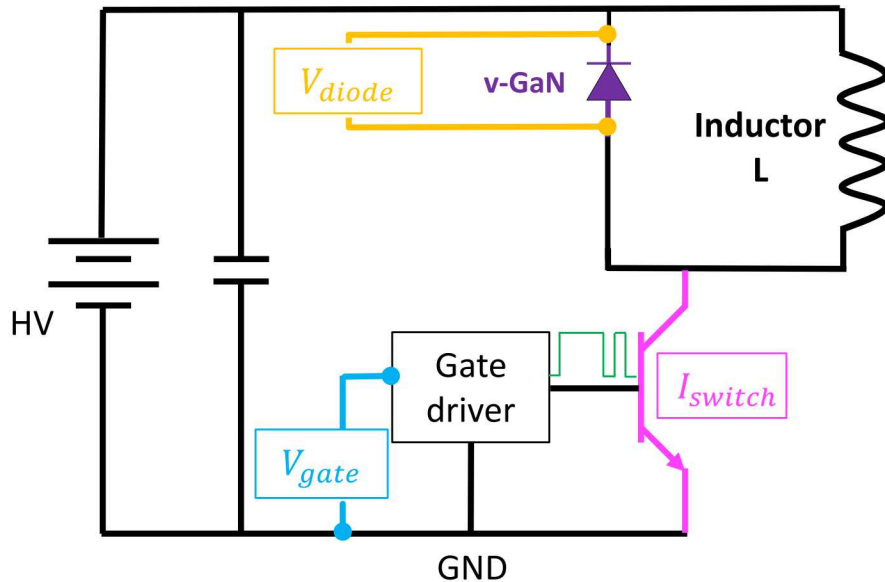
Double-pulse



- 1st gate pulse: Increase stored energy in inductor – “charge up” to quasi-steady-state
- Gate off: Current circulates through diode/inductor loop
- 2nd gate pulse: Characterize switching transients



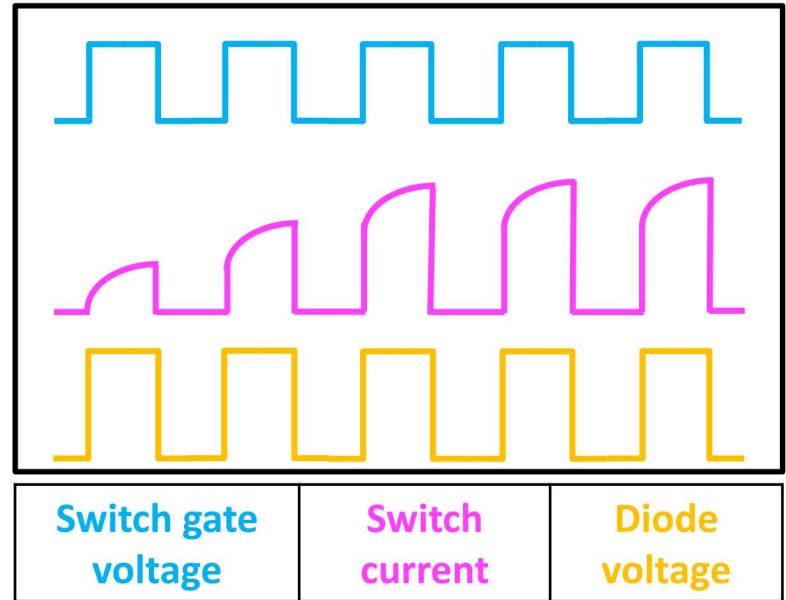
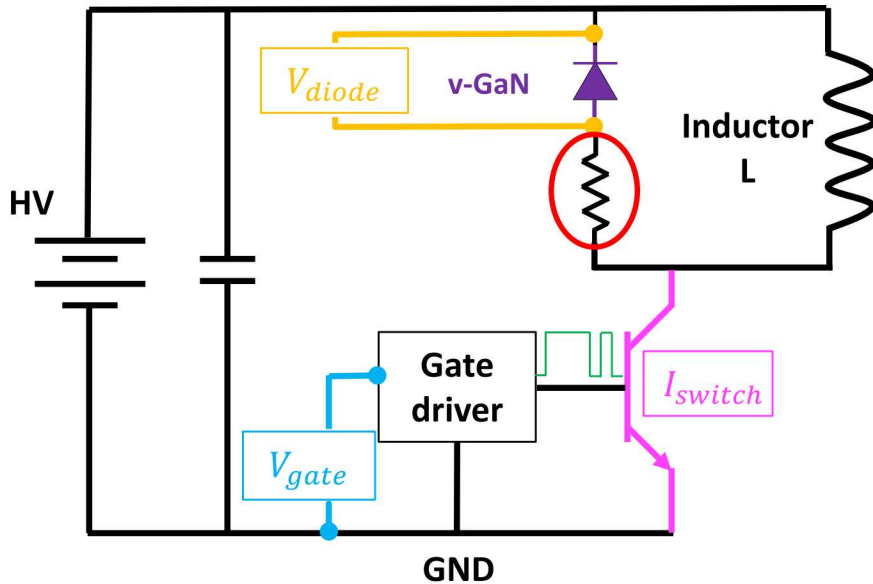
Continuous Waveforms in Ideal DPTC



➤ Idealized analysis of the double-pulse circuit

- All elements are lossless
- Inductor causes current to increase indefinitely
- Not realistic!

Continuous Waveforms in Realistic DPTC

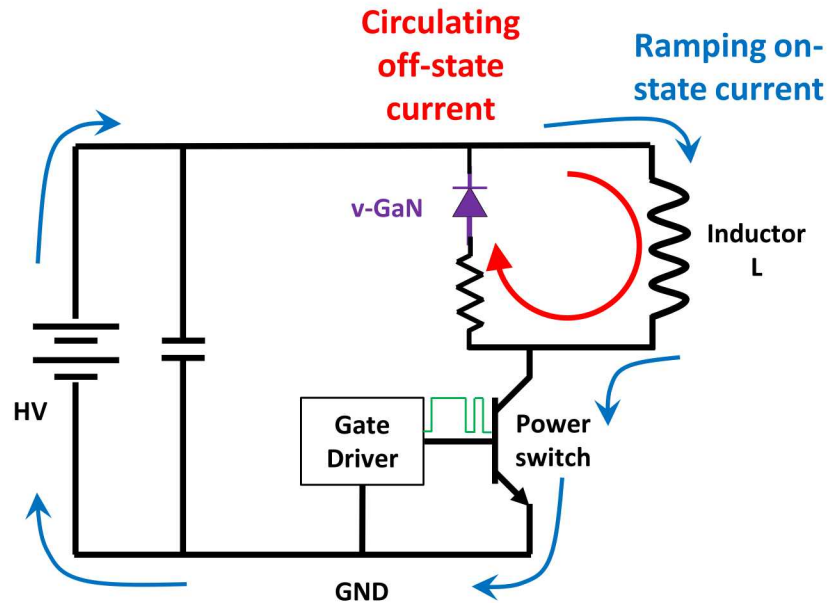


➤ Real circuit has lossy elements

- Represented by lumped resistance in free-wheeling loop
- Causes switch and diode current to saturate
- Realistic DPTC is useful for continuous reliability testing!



Parameters for Steady-State Stress Operation of DPTC



➤ On-state current ramp:

$$\bullet t_{on} = \frac{\Delta I_L \cdot L}{V_{in}}$$

➤ Off-state current in loop:

$$\bullet I_L(t) = I_{max} \cdot e^{-\frac{R}{L}t}$$

➤ Decay time:

$$\bullet t_{off} = -\frac{L}{R} \ln \left(1 - \frac{t_{on} \cdot V_{in}}{L \cdot I_{max}} \right)$$

➤ Switching stress applied for 720 minutes at each of the following supply voltages:

- 500, 750, 1000, 1170 V

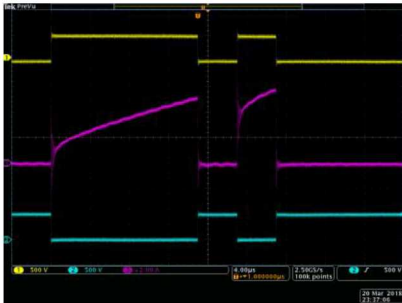
➤ Gate drive conditions

- Switching frequency = 1 kHz, $t_{on} = 2 \mu\text{s}$ (duty = 0.2%)
- $R \approx 1 \Omega$ (parasitic)

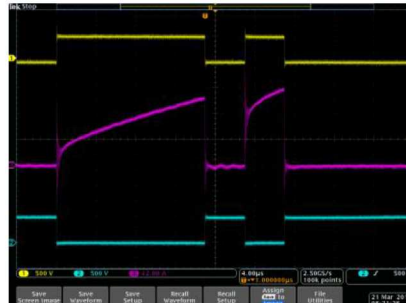


500 V Pulsed Stress Measurements

Double Pulse Pre-Stress



Double Pulse Post-Stress

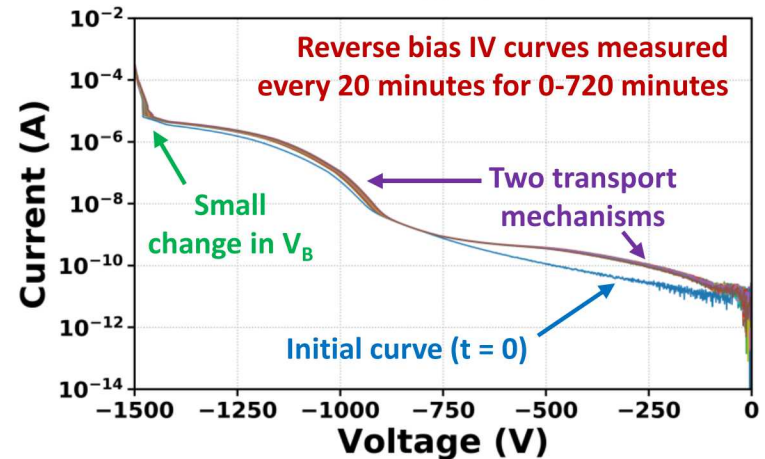
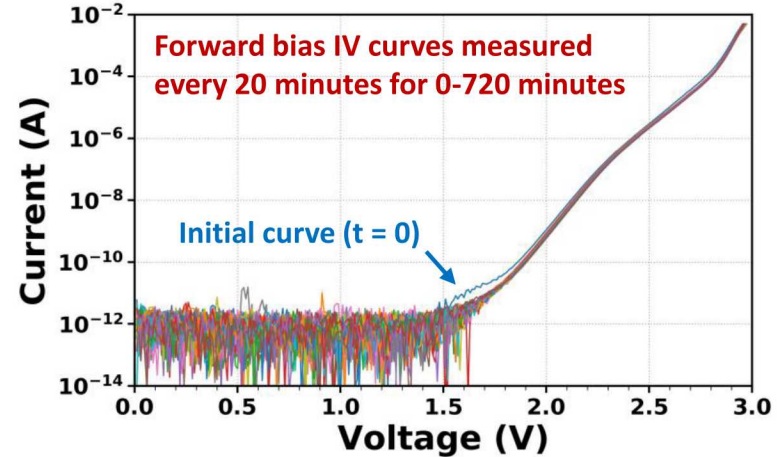


Stress Pulse

Diode voltage

Switch current

Switch D-S voltage

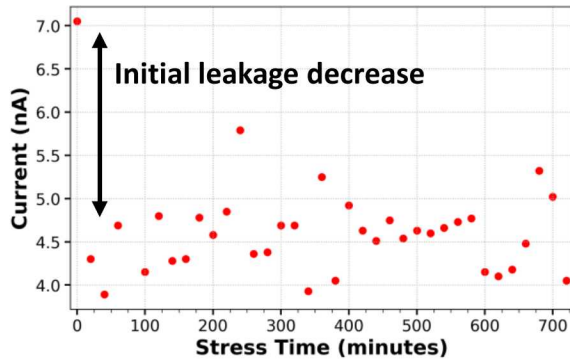


Small initial change in leakage current at lower V_R , followed by very stable operation

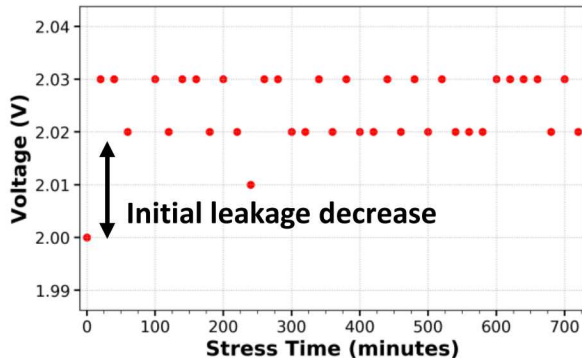
Parametric Drift During 500 V Pulsed Stress

Forward Bias

Forward Bias Current at 2.1 V

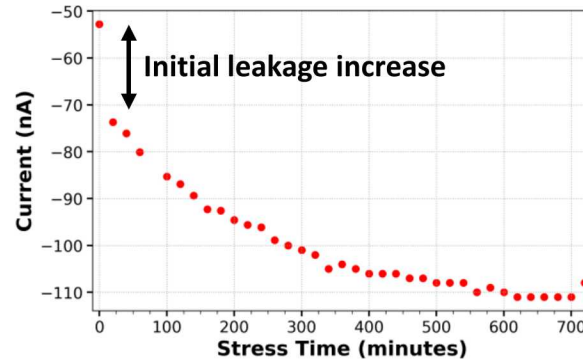


Forward Bias Voltage at 1 nA

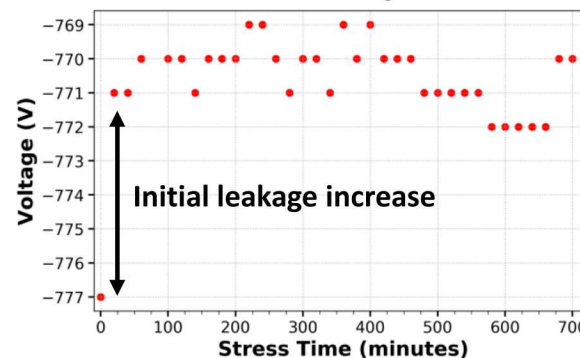


Reverse Bias

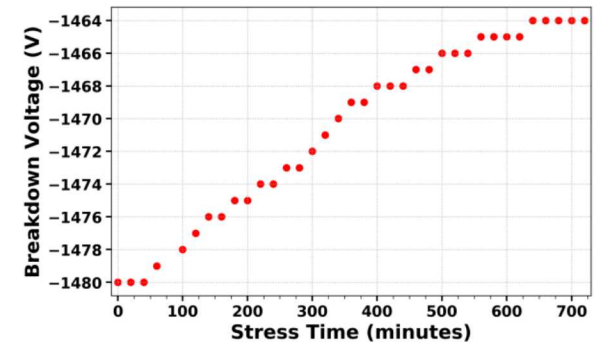
Reverse Bias Current at -1000 V



Reverse Bias Voltage at -1 nA



Breakdown Voltage



Small, monotonic decrease in breakdown voltage with stress time

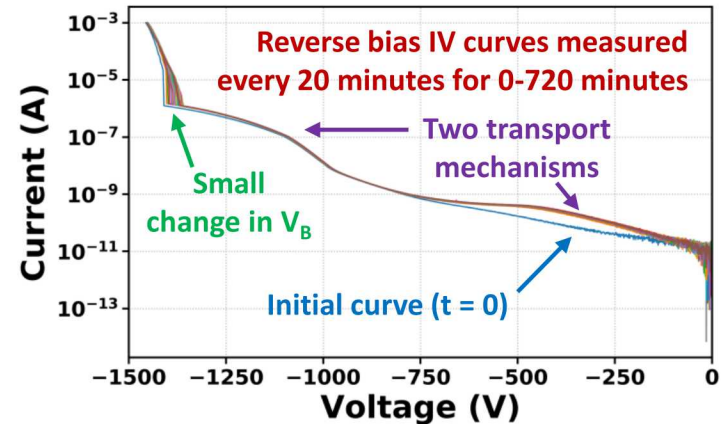
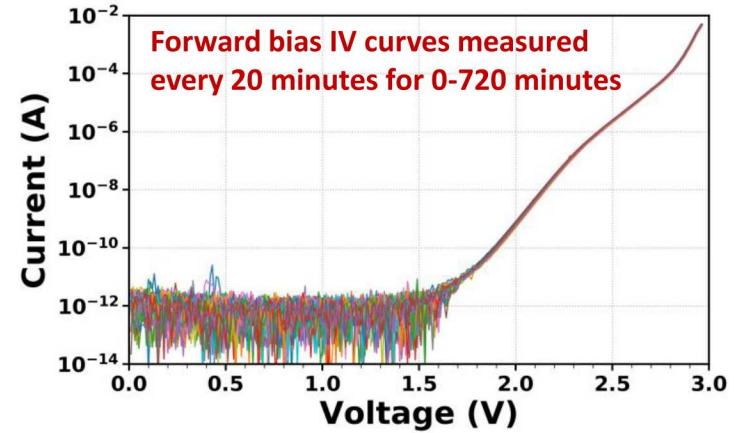
Small initial change in leakage current, followed by very stable operation

750 V Pulsed Stress Measurements

Double Pulse Pre-Stress



Double Pulse Post-Stress

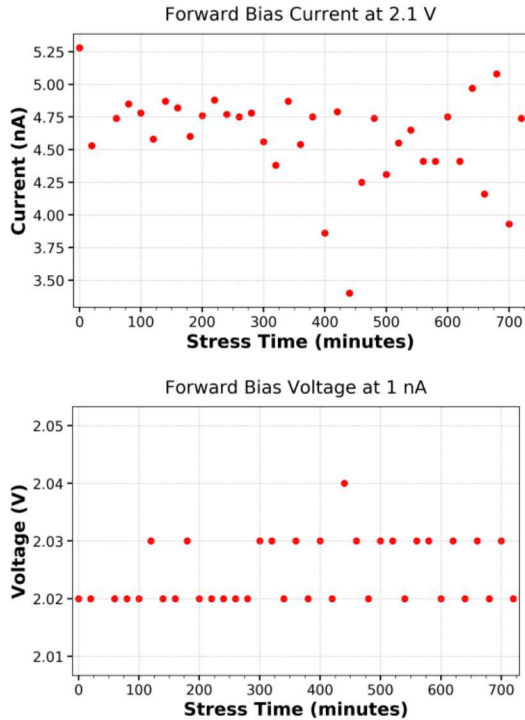


Stress Pulse

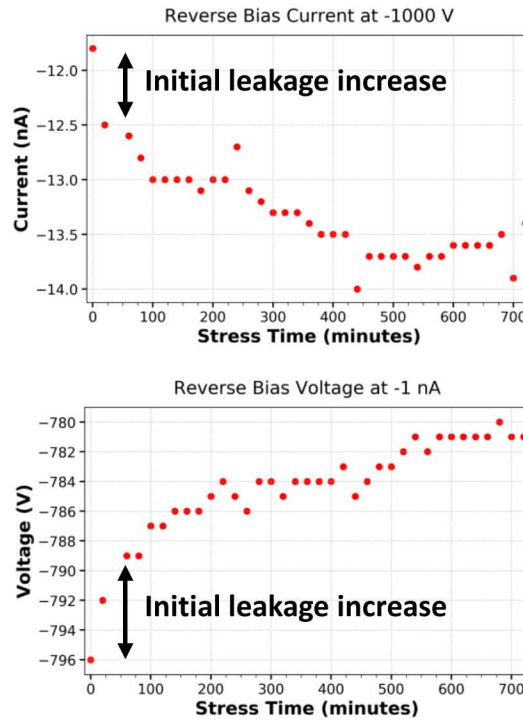
- Initial change in leakage similar to 500 V stress
- Small reduction in V_B with stress time

Parametric Drift During 750 V Pulsed Stress

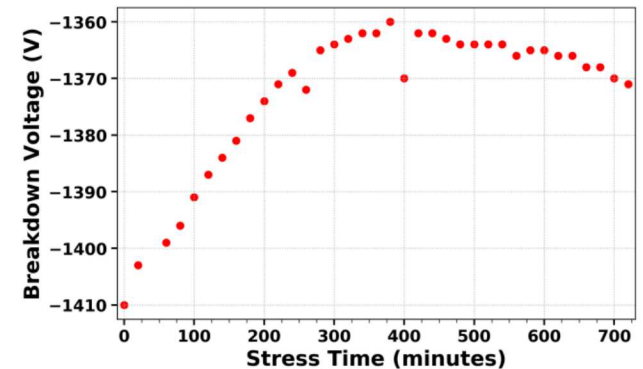
Forward Bias



Reverse Bias



Breakdown Voltage

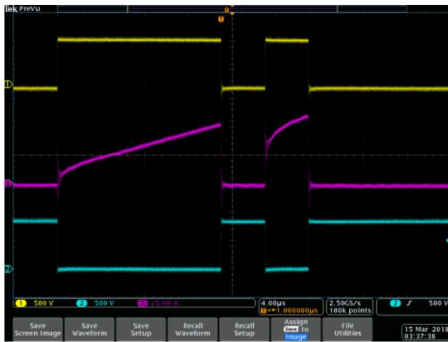


- Initial decrease in breakdown voltage
- Saturates and reverses midway through stress

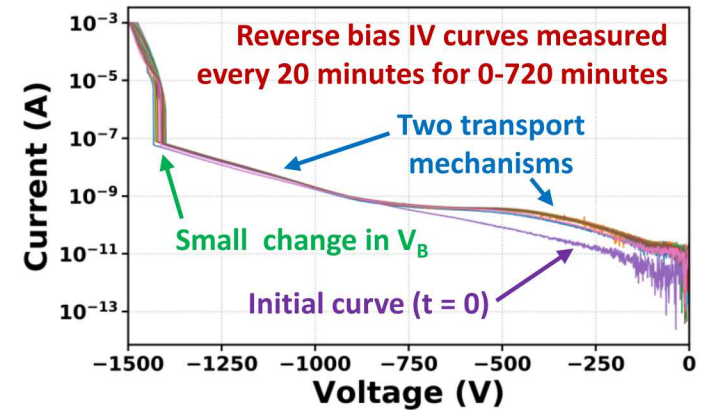
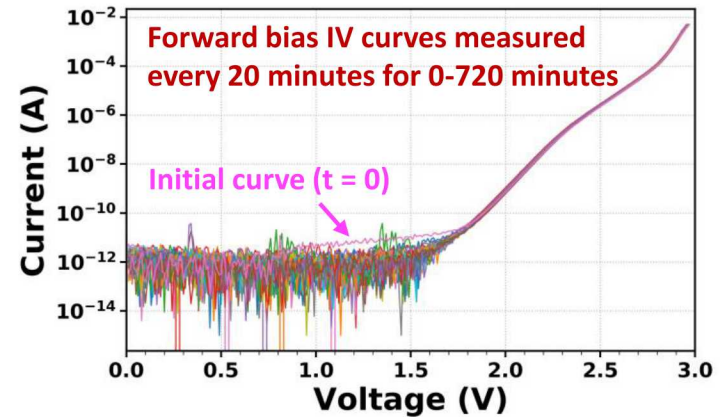
Small initial change in reverse leakage current, followed by stable operation

1000 V Pulsed Stress Measurements

Double Pulse Pre-Stress



Double Pulse Post-Stress



Results are similar to 750 V stress case

Diode voltage

Switch current

Switch D-S voltage

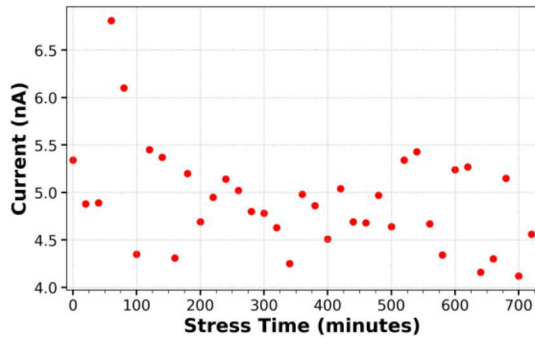


Stress Pulse

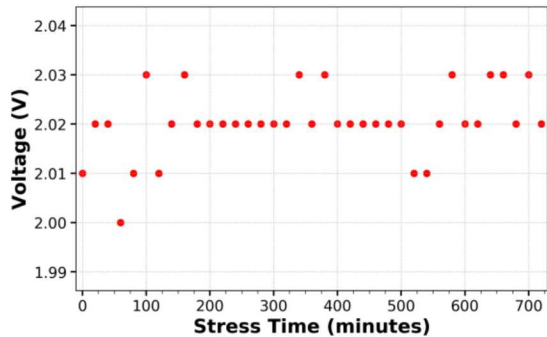
Parametric Drift During 1000 V Pulsed Stress

Forward Bias

Forward Bias Current at 2.1 V

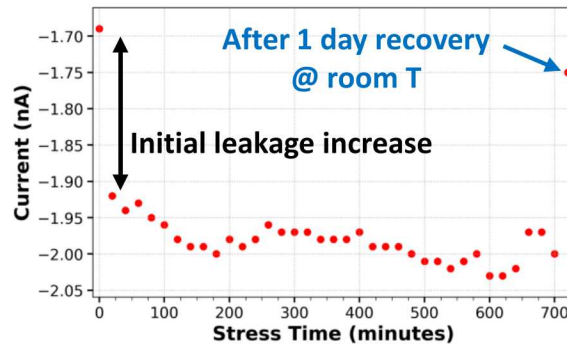


Forward Bias Voltage at 1 nA

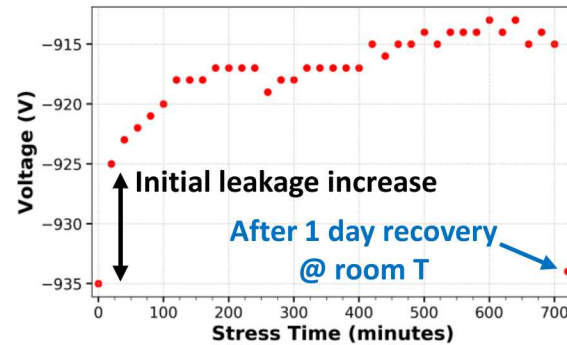


Reverse Bias

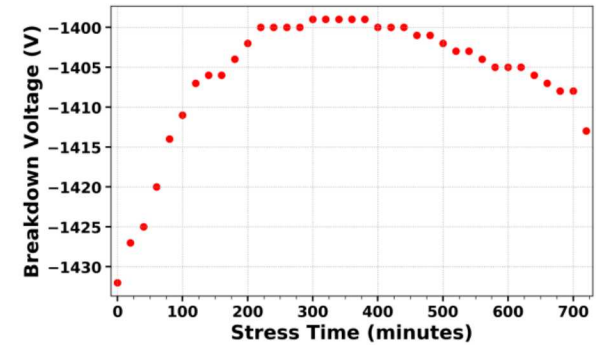
Reverse Bias Current at -1000 V



Reverse Bias Voltage at -1 nA



Breakdown Voltage

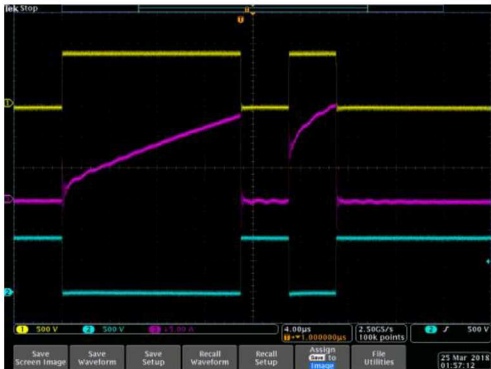


Breakdown behavior is similar to 750 V case

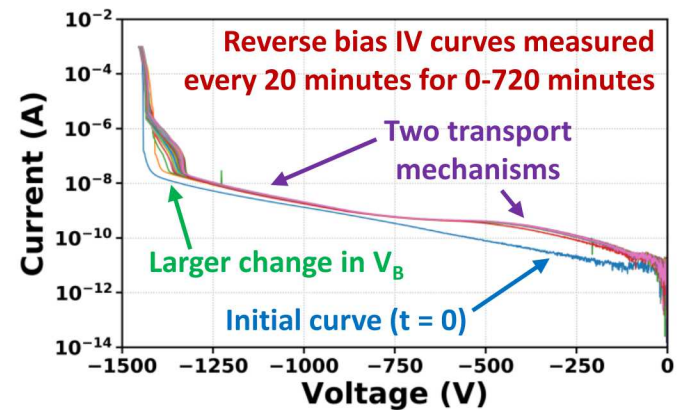
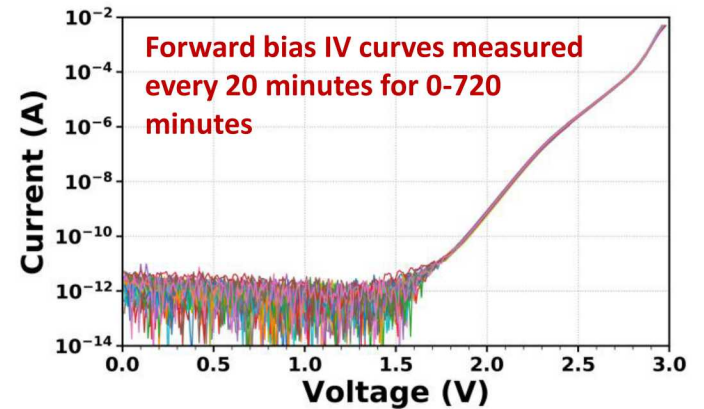
- Behavior is similar to 750 V stress case
- Thermal recovery suggests that degradation mechanism involves carrier trapping

1170 V Pulsed Stress Measurements

**Double Pulse
Pre-Stress**



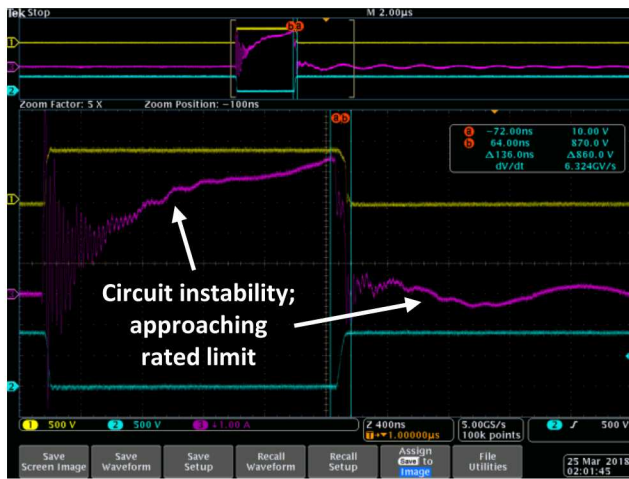
**Double Pulse
Post-Stress**



Diode voltage

Switch current

Switch D-S voltage

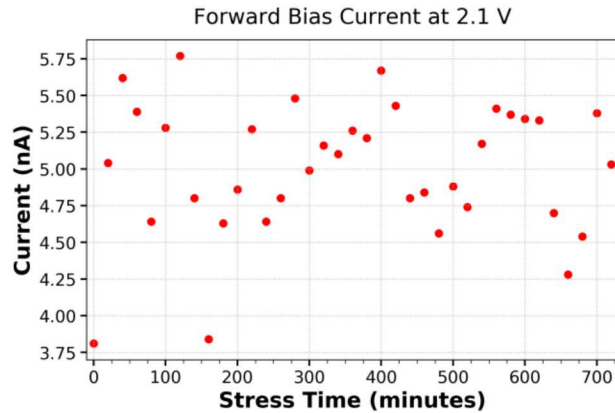


Stress Pulse

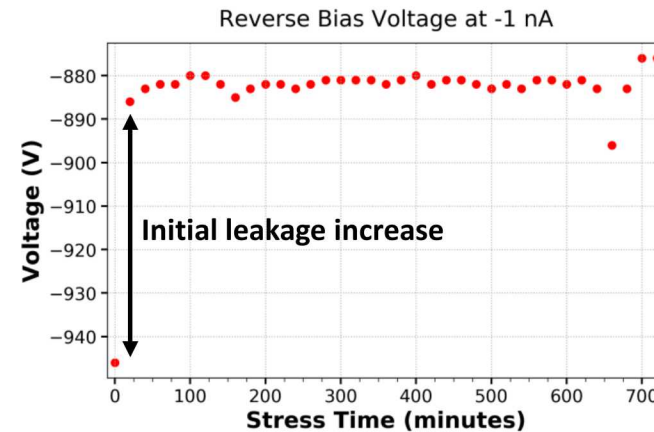
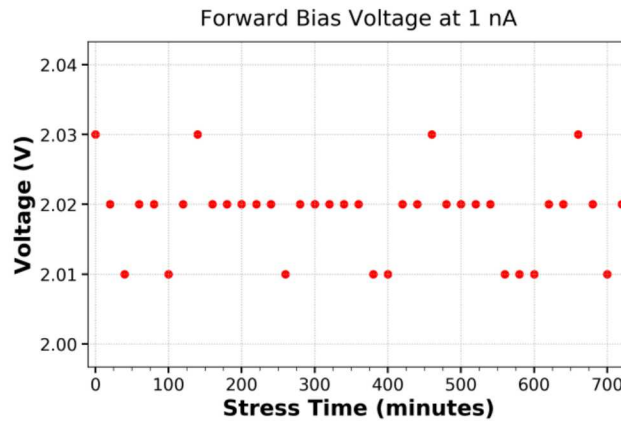
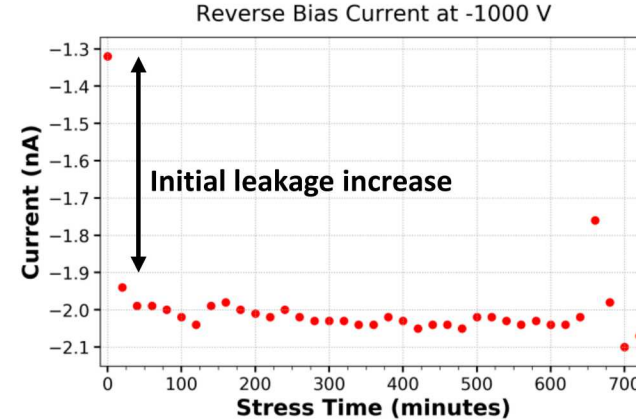
- Leakage results similar to lower V stress cases
- Change in V_B is larger and more complex

Parametric Drift During 1170 V Pulsed Stress

Forward Bias

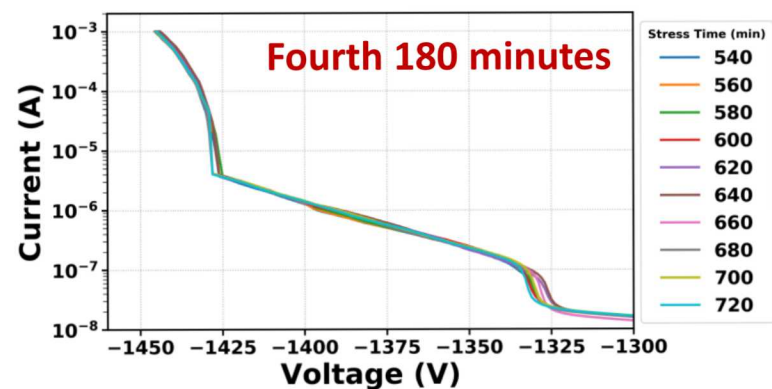
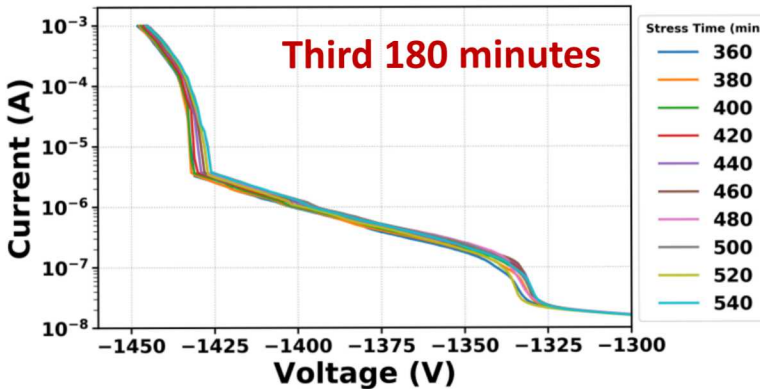
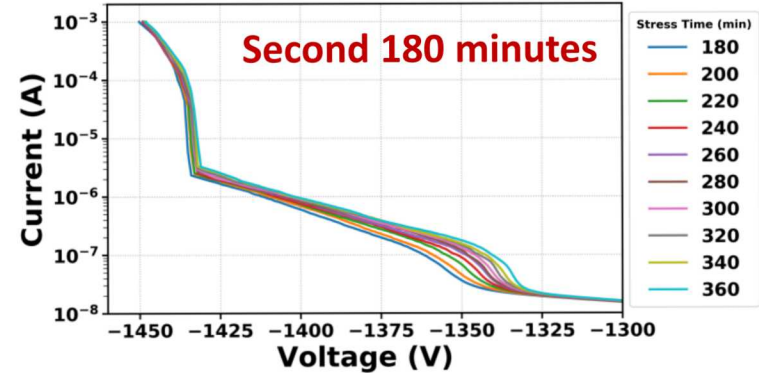
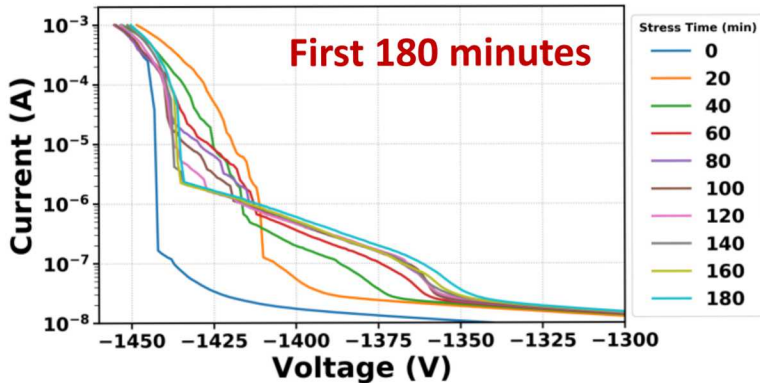


Reverse Bias



Again, small initial change in reverse leakage current, followed by stable operation

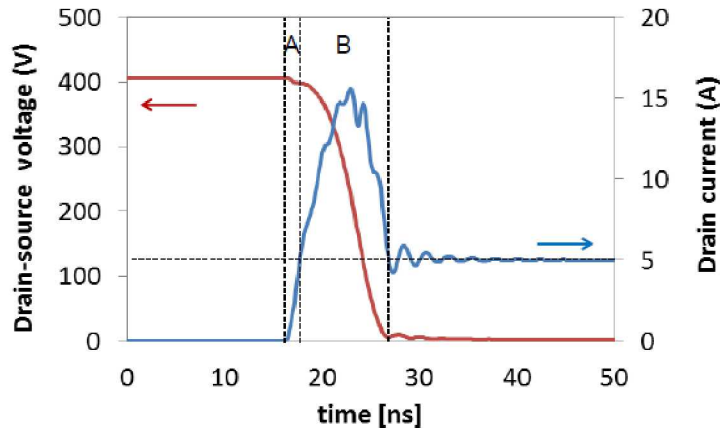
Evolution of Breakdown Voltage During 1170 V Pulsed Stress



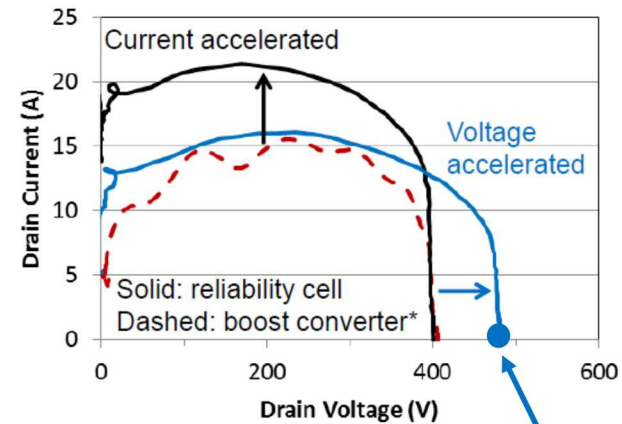
- Looks like “soft” and “hard” breakdown mechanisms evolve with stress time
- Most change occurs within first 180 minutes

Related Topic: Hard-Switching Reliability of Power GaN HEMTs

Hard-switching waveforms – current overshoot, and overlap of high current and high voltage



Switching locus – many voltage/current combinations experienced during switching



HEMTs subjected to many forms of stress during hard-switching:

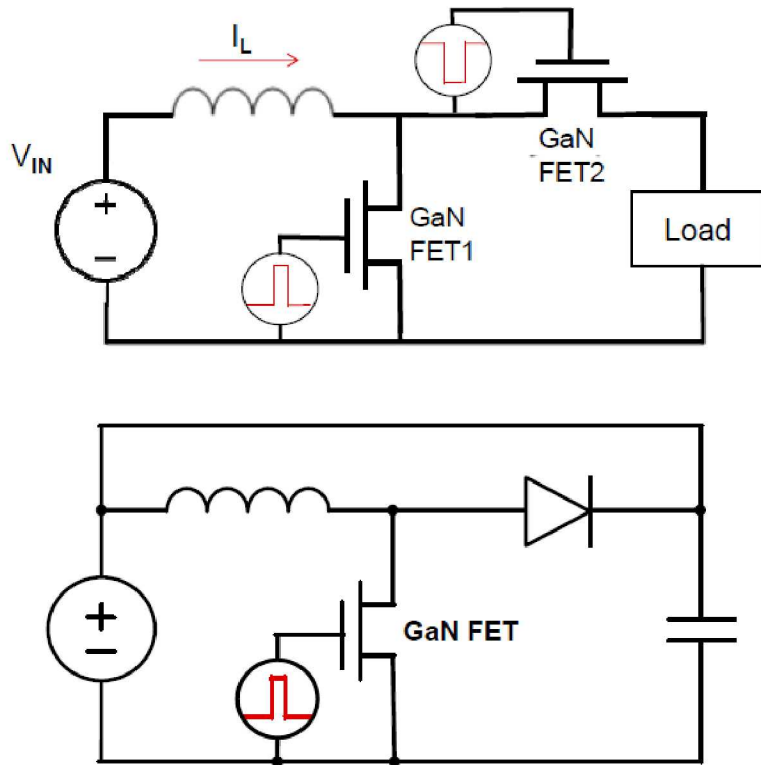
- Hot-carrier effects
- Time-dependent dielectric breakdown
- Over-current due to fast dV/dt
- High power dissipation

Traditional HTRB static test point

- Completely inadequate to test for the range of conditions experienced by the device during hard switching!

New JEDEC Guidelines Will Incorporate Hard-Switching Reliability Testing

Another way to look at the DPTC – a boost converter with the input and output tied together



Newly-formed JEDEC committee JC70.1 is creating guidelines towards standardization of reliability evaluation for GaN power devices

- **Several important topics identified, one of which is hard switching reliability**
- **New tests will compliment traditional tests such as HTRB**
- **Will evaluate the entire switching locus and will thus encompass effects such as hot-carrier degradation and TDDB**
- **DPTC circuit proposed as standard test vehicle**
- **Broad international input from industry, academia, and national labs**

Summary

- **Vertical GaN may offer advantages compared to SiC and lateral GaN**
 - Higher critical electric field
 - Avalanche breakdown
 - Early research stage, many outstanding questions including reliability
- **Utilized double-pulse test circuit to evaluate switching reliability of 1200 V Avogy vertical GaN PiN diodes**
 - Tested at 500, 750, 1000, and 1170 V in continuous-pulse mode
 - Reverse leakage at low bias increases after short stress time and saturates
 - Recovers after sitting for a day – suggests trapping mechanism is responsible
 - Breakdown voltage decreases slightly with stress time, and may recover or show “soft” and “hard” behavior depending on stress voltage
 - *Overall, the devices are robust over the range of conditions tested*
- **The same circuit may be used for reliability testing of GaN HEMTs**
 - JEDEC is examining this for standardization – JC70.1

*We thank the DOE Office of Electricity Energy Storage Program,
managed by Dr. Imre Gyuk, for funding the work at Sandia National Labs*